## **Supporting Information**

A low temperature and air-sinterable copper-diamine complexbased metal organic decomposition ink for printed electronics Yue Dong<sup>1,2</sup>, Zhijie Lin<sup>1,2,3</sup>, Xiaodong Li<sup>1,2\*</sup>, Qi Zhu<sup>1,2</sup>, Ji-Guang Li<sup>1,2,4</sup>, Xudong Sun<sup>1,2,5</sup> <sup>1</sup>Key Laboratory for Anisotropy and Texture of Materials (Ministry of Education), Northeastern University, Shenyang, Liaoning 110819, China

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**Fig. S1** FTIR speatra of amine, Cuf-amine complex and films heated from 90-150 °C: (a) EA, (b) PA, (c) BA, (d) HA, (e) EDA.



Fig. S2 XRD patterns of Cuf·4H<sub>2</sub>O powder heated at 300 °C for 1 min.



Fig. S3 TG and DSC curves of ink complex with (a) EA, (b) PA, (c) HA and (d) EDA.



Fig. S4 Photos of films heated at various temperatures from (a) Cuf-BA ink, (b) Cuf-PDA ink.



Fig. S5 UV-vis spectra of Cuf-amine complex with various amines.

Temperature (°C)	Time (min)	Sheet resistance ( $\Omega$ /sq)	Thickness (µm)	Resistivity ( $\Omega \cdot cm$ )
130	1	3.361	1.22	4.1×10 <sup>-4</sup>
	5	1.186	1.18	1.4×10 <sup>-4</sup>
	10	1.024	1.27	1.3×10 <sup>-4</sup>
	20	0.968	1.24	1.2×10 <sup>-4</sup>
	30	0.728	1.14	8.3×10 <sup>-5</sup>
	40	0.712	1.11	7.9×10 <sup>-5</sup>
	60	0.542	1.31	7.1×10 <sup>-5</sup>
150	1	0.778	1.26	9.8×10 <sup>-5</sup>
	5	0.398	1.18	4.7×10 <sup>-5</sup>
	10	0.556	1.15	6.4×10 <sup>-5</sup>
	20	0.696	1.25	8.7×10 <sup>-5</sup>
	30	0.722	1.26	9.1×10 <sup>-5</sup>
	40	0.736	1.29	9.5×10 <sup>-5</sup>
	60	1.034	1.16	1.2×10 <sup>-4</sup>
180	1	0.162	1.11	1.8×10 <sup>-5</sup>
	5	0.333	1.23	4.1×10 <sup>-5</sup>
	10	0.556	1.26	7.0×10 <sup>-5</sup>
	20	0.846	1.30	1.1×10-4
	30	0.945	1.27	1.2×10 <sup>-4</sup>
	40	1.167	1.20	1.4×10 <sup>-4</sup>
	60	1.270	1.26	1.6×10 <sup>-4</sup>
200	1	0.432	1.18	5.1×10 <sup>-5</sup>
	5	0.765	1.15	8.8×10 <sup>-5</sup>
	10	1.322	1.21	1.6×10 <sup>-4</sup>
	20	1.550	1.29	2.0×10 <sup>-4</sup>
	30	2.203	1.18	2.6×10 <sup>-4</sup>
	40	2.541	1.22	3.1×10-4

**Table S1.** The sheet resistance, thickness and resistivity of films heated at various temperatures for different time.

250	60	3.047	1.28	3.9×10 <sup>-4</sup>
	1	6.807	1.19	8.1×10 <sup>-4</sup>
	5	35.200	1.25	4.4×10-3
	10	93.023	1.29	1.2×10 <sup>-2</sup>
	20	1092.437	1.19	1.3×10 <sup>-1</sup>
	30	1282.051	1.17	1.5×10 <sup>-1</sup>
	40	1382.114	1.23	1.7×10 <sup>-1</sup>
	60	1417.323	1.27	1.8×10-1
300	1	24793.388	1.21	3.0
	5	44067.797	1.18	5.2
	10	48412.698	1.26	6.1
	20	59689.922	1.29	7.7
	30	80645.161	1.24	10.0
	40	81102.362	1.27	10.3
	60	88983.051	1.18	10.5



Fig. S6 FTIR spectra of films heated from various temperatures from Cuf-PDA ink in Ar.



Fig. S7 Viscosity and contact angle of Cuf-PDA.